

PART ONE: General description

Lithography5

Process name

YH3_001

Process Code

04/25/00

Last Update

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Author

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Contact Information (Email)

AZ1512 for lift-off of very thin film (~20 nm).

General description of process

PART TWO: Details

Cleaning

Nano-strip

10

Time (min)

BOE

1

Time (min)

Rinse and Dry

Wet Oxidation

~4600

Thickness (nm)

Resist Coating

P-10

Primer

500

Speed1 (RPM)

5

Time(sec)

3000

Speed2 (RPM)

30

Time(sec)

HMDS

AZ 1512

Resist

500

Speed1 (RPM)

5

Time(sec)

3000

Speed2 (RPM)

30

Time(sec)

PreBake

Hot Plate

95

T (°C)

2

Time(min)

Exposure

3" Aligner

20

Time(sec)

Develop

AZ351:H2O (1:4)

Developer

60

Time(sec)

PostBake

Oven

T (°C)

Time(min)

Rinse and Dry

PART THREE: General Comments

4" aligner - 15 sec exposure
AZ 1518 22/27 sec exposure for 4/3" aligners.